

User Name & ID (Print):

PI (subject to change):

User Signature & Date:

Research Focus (subject to change):

User e-mail:

Extreme Hazards	Process Name	User Initials	Qualifier Initials	Date	User Initials	Qualifier Initials	Date	User Initials	Qualifier Initials
	Acetic Acid, Glacial								
	Ammonium Fluoride								
	Ammonium Hydroxide								
	Aqua Regia								
	Buffered Oxide Etch								
	HNA								
	Hydrochloric Acid (HCl)								
	Hydrofluoric Acid (HF)								
	Hydrogen Peroxide								
	Nitric Acid								
	PAN								
	Phosphoric Acid								
	Piranha								
	Potassium Hydroxide								
	RCA1 (Base)								
	RCA2 (Acid)								
SulphoNitric									
Sulphuric Acid									

Chemical Handling and Equipment	Process Name	User Initials	Qualifier Initials	Date	User Initials	Qualifier Initials	Date	User Initials	Qualifier Initials
	Breadth of Hazards								
	Haz Waste Management								
	Labeling Experiments								
	Pouring and Mixing								
	PPE Choice & Cleaning								
	Sharps								
	Work Station Use								
	KOH Bath								
	RCA Bath								
	Sonicators								
	Stir- and Hotplates								

**Users:** By initialing, you agree that you understand and will follow the SOP.

If you forget any rules it is your responsibility to seek help from the lab staff, who will happily provide further trainin

User Name & ID (Print):

	Process Name	User	Qualifier	Date	User	Qualifier	Date	User	Qualifier
		Initials	Initials		Initials	Initials		Initials	Initials
Tools	Alcatel DRIE								
	Cannon Aligner								
	CHA E-beam Evaporator								
	CHA Sputterer								
	CPD								
	Dektak 3030 and/or 2A								
	Dicing Saw								
	EVG Aligner								
	FEI NanoSEM								
	FirstNano Nanowire CVD								
	Karl Suss MA-4								
	Lesker Sputter								
	Mann PG								
	MRL Furnace								
	Nanonex								
	PlasmaTherm Etcher								
	RTP								
	Solitec Spinner/Hotplate								
	Spin Rinsers								
	Technics PECVD								
Technics RIE									
UV Flood									

	Process Name	User	Qualifier	Date	User	Qualifier	Date	User	Qualifier
		Initials	Initials		Initials	Initials		Initials	Initials
Common Lesser Hazards	Aqueous Developers								
	Chrome Etch								
	DMSO								
	EBL Developer								
	Halogenated Solvents								
	Monolayer Deposition								
	PR Diluents & Strippers								
	Squirt Bottle Solvents								
	Standard Photoresists								

Users: By initialing, you agree that you understand and will follow the SOP.

If you forget any rules it is your responsibility to seek help from the lab staff, who will happily provide further trainin





